# ECE 371 Materials and Devices

10/08/19 - Lecture 13
Intrinsic and Extrinsic
Semiconductors

#### **General Information**

Homework 4 assigned, due Tuesday 10/15

Homework 3 solutions posted

Midterm solutions posted

Reading for next time: 4.3-4.5

#### **Equilibrium Carrier Concentrations**

Thermal Equilibrium: no external forces (e.g., voltages, electric fields, magnetic fields, temperature gradients, act on the semiconductor. Properties are time independent.

Equilibrium electron and hole concentrations:

$$n_0 = N_c \exp\left[\frac{-(E_c - E_F)}{kT}\right]$$

$$p_0 = N_v \exp\left[\frac{-(E_F - E_v)}{kT}\right]$$

Effective density of states:

$$N_c = 2\left(\frac{2\pi m_n^* kT}{h^2}\right)^{\frac{3}{2}}$$
  $N_v = 2\left(\frac{2\pi m_p^* kT}{h^2}\right)^{\frac{3}{2}}$ 

$$N_v = 2\left(\frac{2\pi m_p^* kT}{h^2}\right)^{\frac{3}{2}}$$

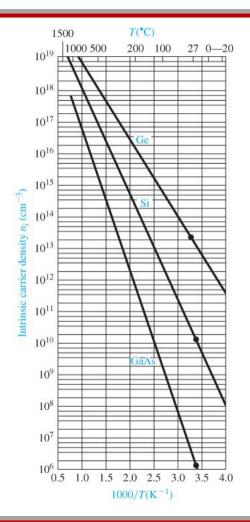
	N <sub>c</sub> (cm <sup>-3</sup> )	N <sub>v</sub> (cm <sup>-3</sup> )	m <sub>n</sub> */m <sub>0</sub>	m <sub>p</sub> */m <sub>0</sub>
Si	2.8e19	1.04e19	1.08	0.56
GaAs	4.7e17	7.0e18	0.067	0.48
Ge	1.04e19	6.0e18	0.55	0.37

#### Intrinsic Carrier Concentration

- Intrinsic semiconductor: no impurities
- # electrons in conduction band = # holes in valence band
- $n_i$  is the intrinsic carrier concentration
- $E_{Fi}$  is the intrinsic Fermi level
- $E_q$  is the band gap energy

$$n_i^2 = N_c N_v \exp\left[-\frac{E_g}{kT}\right]$$

T = 300 K	E <sub>g</sub> (eV)	n <sub>i</sub> (cm <sup>-3</sup> )
Si	1.12	1.5e10
GaAs	1.42	1.8e6
Ge	0.66	2.4e13



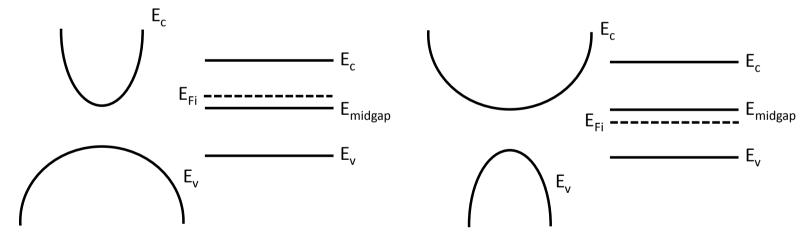
# Intrinsic Fermi Level (E<sub>Fi</sub>)

$$E_{Fi} - E_{midgap} = \frac{3}{4}kT \ln \left(\frac{m_p^*}{m_n^*}\right)$$

$$m_n^* = m_p^* \Rightarrow E_{Fi}$$
 is at midgap

 $m_n^* < m_p^* \Rightarrow E_{Fi}$  is above midgap

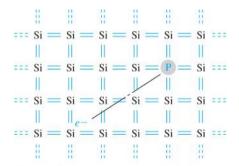
 $m_n^* > m_p^* \Rightarrow E_{Fi}$  is below midgap



 $E_{Fi}$  must shift away from the band with the higher DOS (m\*) to maintain  $n_0 = p_0$ 

# Extrinsic Semiconductors (n-type)

- Extrinsic Semiconductor: addition of intentional impurities (dopants) to control conduction properties
- N-type semiconductors primarily conduct current using electrons in the conduction band
- In silicon, a phosphorus (P) atom donates an electron to the lattice → "donor"
- P is group V and uses 4 valence electrons to bond with silicon
- The last valence electron is weakly bound to the phosphorus atom and can be elevated to the conduction band (i.e. – unbound from the P atom) with some thermal energy



**Figure 4.4** | Two-dimensional representation of the silicon lattice doped with a phosphorus atom.

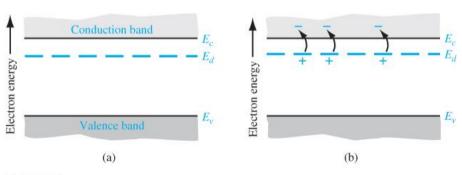


Figure 4.5 | The energy-band diagram showing (a) the discrete donor energy state and (b) the effect of a donor state being ionized.

### Extrinsic Semiconductors (p-type)

- P-type semiconductors primarily conduct current using holes in the valence band
- In silicon, a boron (B) atom accepts an electron from the lattice → "acceptor"
- B is group III and uses 3 valence electrons to bond with silicon
- It takes an additional valence electron from the lattice, leaving a hole
- Removal of an electron from the lattice requires some thermal energy
- The empty state left behind can propagate through the crystal and generate current

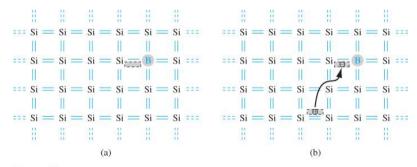


Figure 4.6 | Two-dimensional representation of a silicon lattice (a) doped with a boron atom and (b) showing the ionization of the boron atom resulting in a hole.

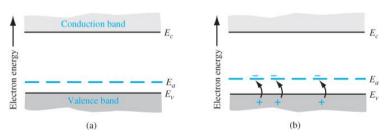


Figure 4.7 | The energy-band diagram showing (a) the discrete acceptor energy state and (b) the effect of an acceptor state being ionized.

#### **Ionization Energy**

- Energy required to remove a weakly bound electron from the lattice and put it in the conduction band is called "ionization energy"
- Similarly, the energy required to elevate an electron from the lattice into an acceptor level also has an ionization energy (holes)
- Some dopants can function as donors AND acceptors. These are called *amphoteric dopants*. An example is a Si dopant in a GaAs lattice.

Table 4.3 | Impurity ionization energies in silicon and germanium

	Ionization energy (eV)		
Impurity	Si	Ge	
Donors			
Phosphorus	0.045	0.012	
Arsenic	0.05	0.0127	
Acceptors			
Boron	0.045	0.0104	
Aluminum	0.06	0.0102	

Table 4.4 | Impurity ionization energies in gallium arsenide

Impurity	Ionization energy (eV)	
Donors		
Selenium	0.0059	
Tellurium	0.0058	
Silicon	0.0058	
Germanium	0.0061	
Acceptors		
Beryllium	0.028	
Zinc	0.0307	
Cadmium	0.0347	
Silicon	0.0345	
Germanium	0.0404	

# Extrinsic Semiconductors (Fermi Level)

- Addition of dopant atoms changes the position of the Fermi energy
  - For  $E_F > E_{Fi} \rightarrow n > p \rightarrow n$ -type
  - For  $E_F$  <  $E_{Fi}$  → p > n → p-type

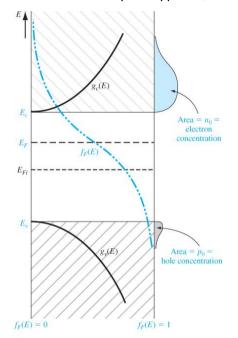


Figure 4.8 | Density of states functions, Fermi–Dirac probability function, and areas representing electron and hole concentrations for the case when  $E_F$  is above the intrinsic Fermi energy.

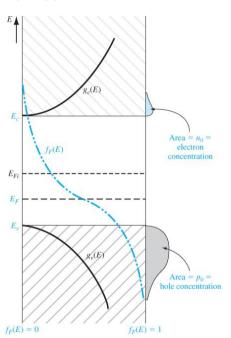


Figure 4.9 I Density of states functions, Fermi–Dirac probability function, and areas representing electron and hole concentrations for the case when 
$$E_F$$
 is below the intrinsic Fermi energy.

$$n_0 = n_i \exp\left[\frac{E_F - E_{Fi}}{kT}\right]$$

$$p_0 = n_i \exp \left[ \frac{-(E_F - E_{Fi})}{kT} \right]$$

# The n<sub>0</sub>\*p<sub>0</sub> Product

- The product of  $n_0$  and  $p_0$  is always a constant for a given material at a given temperature
- The following relationship was derived under the Boltzmann approximation

$$n_0 p_0 = n_i^2$$

#### Degenerate Semiconductors

- Nondegenerate individual dopant atoms are far apart and do not interact. Spacing between dopants is large.
- Degenerate concentration of dopant atoms is high and individual dopant atoms interact, splitting the dopant energies into a band.
- $E_F$  can move into the conduction or valence band if  $n_0 > N_c$  or  $p_0 > N_v$ , respectively. This leads to a large electron or hole concentration.

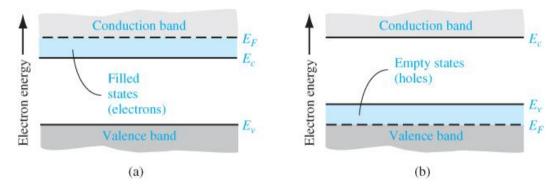


Figure 4.11 | Simplified energy-band diagrams for degenerately doped (a) n-type and (b) p-type semiconductors.

#### Exercise Problem 4.5

#### EXERCISE PROBLEM

Ex 4.5 Determine the thermal-equilibrium concentrations of electrons and holes in silicon at T = 300 K if the Fermi energy level is 0.215 eV above the valence-band energy  $E_v$ . ( $\varepsilon_-$  up  $v_0$  1 ×  $v_0$  1 ×  $v_0$  1 ×  $v_0$  2 ×  $v_0$  3 ×  $v_0$ 

### **Donor/Acceptor Statistics**

- Pauli exclusion principle applies to donors and acceptors
- $n_d$  and  $p_a$  are the electron and hole concentrations in donor and acceptor states, respectively
- $E_d$  and  $E_q$  are the donor and acceptor energy levels, respectively
- Factors of  $\frac{1}{2}$  and  $\frac{1}{2}$  are  $\frac{1}{2}$ , where g is the degeneracy factor

$$n_d = \frac{N_d}{1 + \frac{1}{2} exp\left[\frac{E_d - E_F}{kT}\right]} = N_d - N_d^+$$

Electrons in donor states

$$p_a = \frac{N_a}{1 + \frac{1}{4} exp\left[\frac{E_F - E_a}{kT}\right]} = N_a - N_a^-$$

Holes in acceptor states